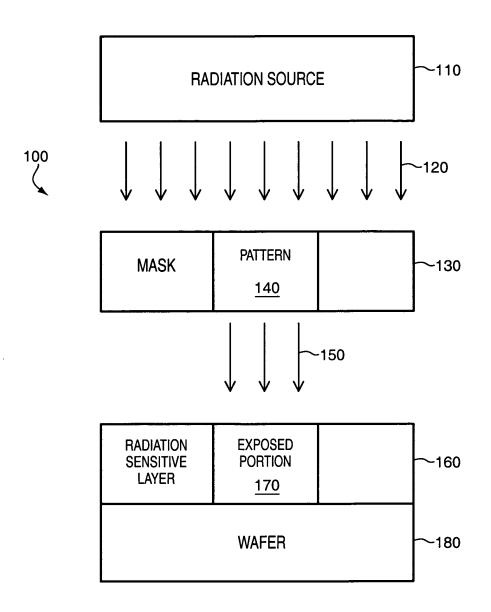


FIG. 1





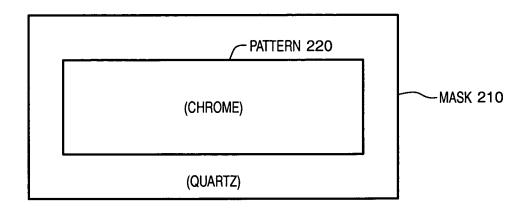


FIG. 2

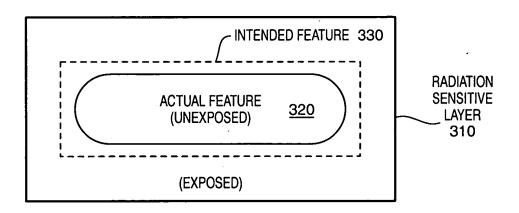


FIG. 3



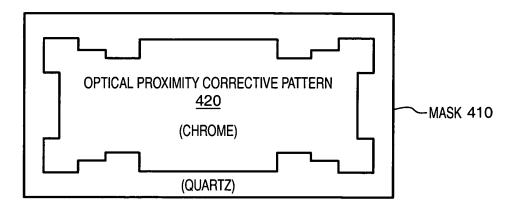


FIG. 4

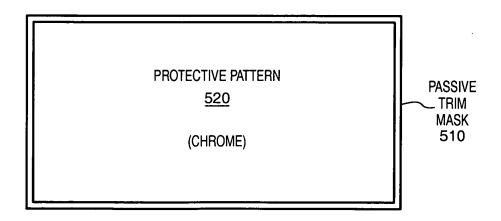
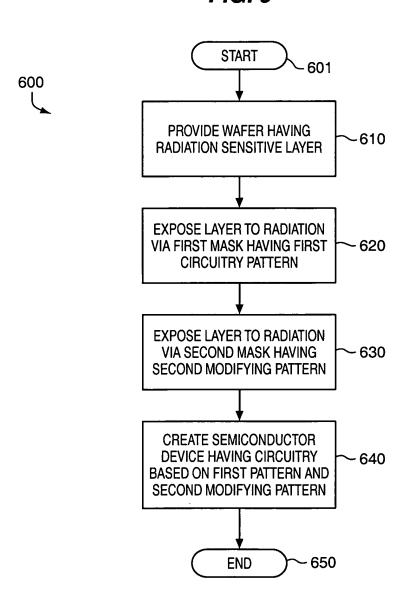


FIG. 5



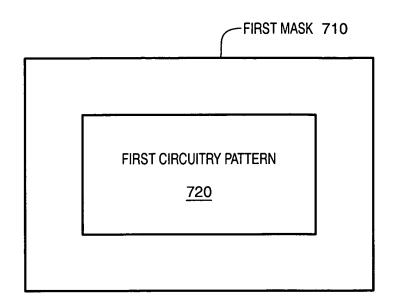
FIG. 6





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SET OF MASKS 700



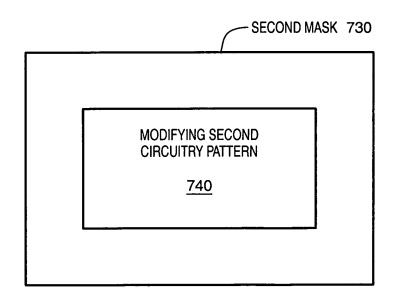
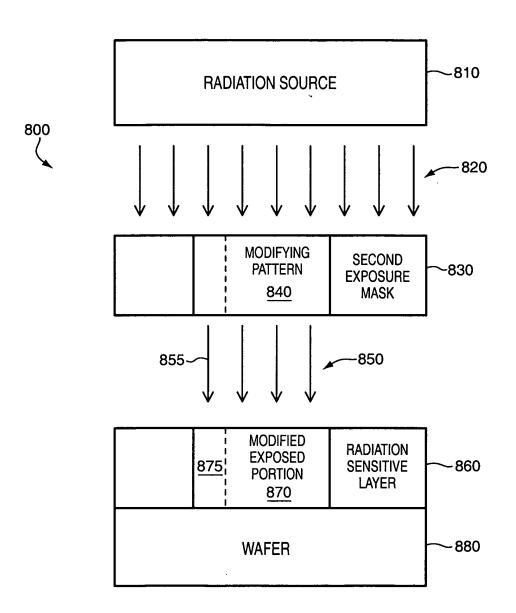




FIG. 8





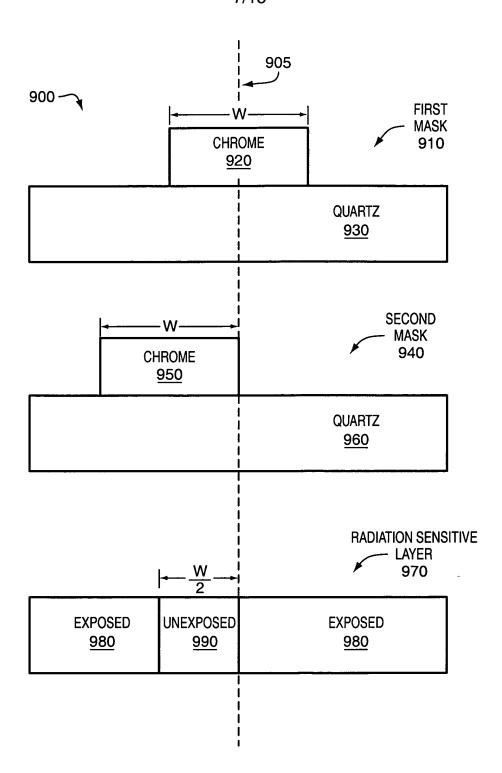


FIG. 9



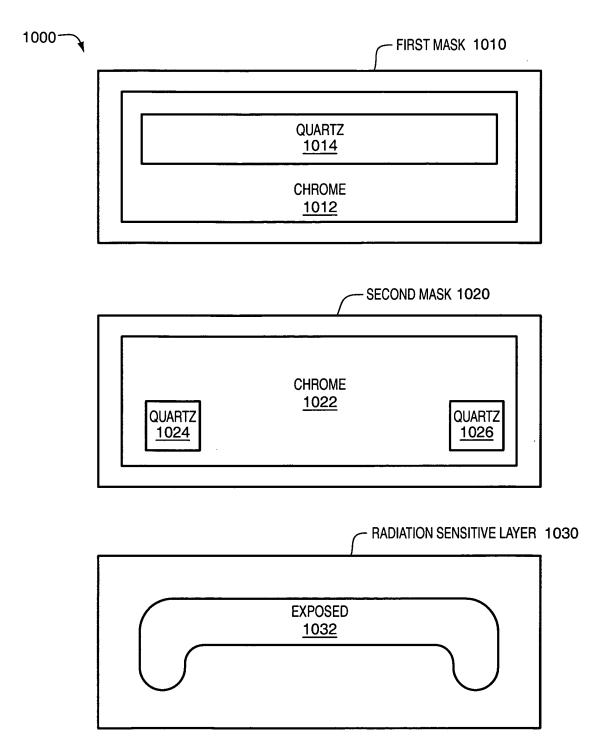


FIG. 10

QUARTZ 1160

PHASE SHIFTING MASK 1150-

BINARY MASK 1110~

1165

1165

QUARTZ 1120

1125

1130

1175~

ELECTRICAL FIELD AT MASK

PHASE SHIFTER 1170



Intensity At Wafer



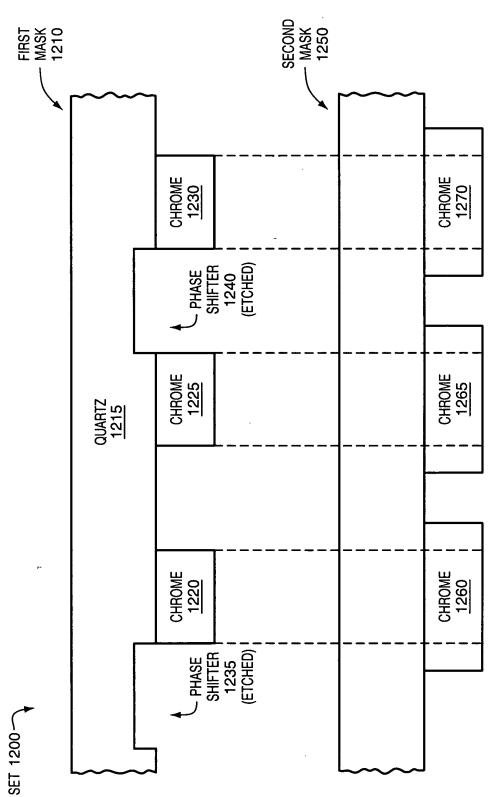
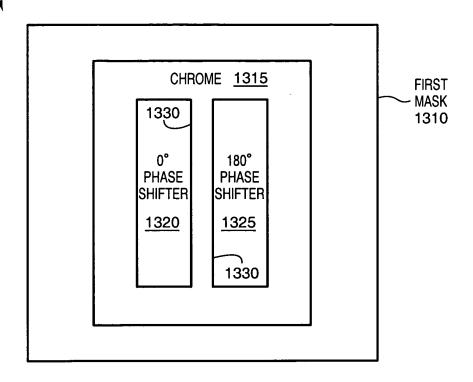


FIG. 12



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SET 1300



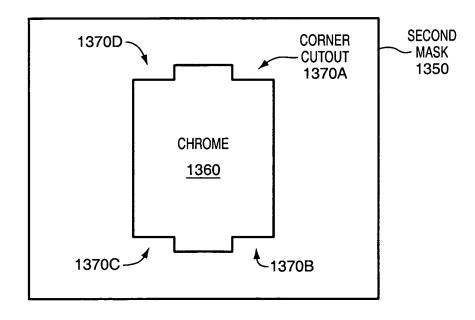


FIG. 13



SET

Title: "An Active Secondary Exposure Mask To Manufacture Integrated Circuits"

Inventors: Fred Chen et al. Application No.: 10/040,772 Attorney Docket No.: 42P11369

Blakely, Sokoloff, Taylor & Zafman 303-740-1980

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FIRST
MASK
1410

LOW
TRANSMITTANCE
REGION
1415
1420

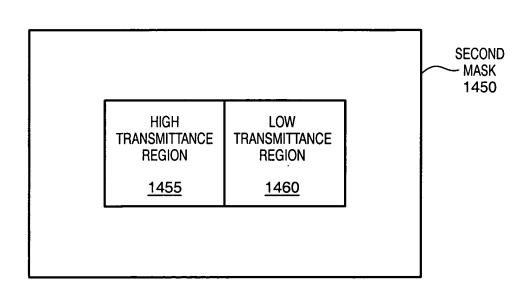


FIG. 14



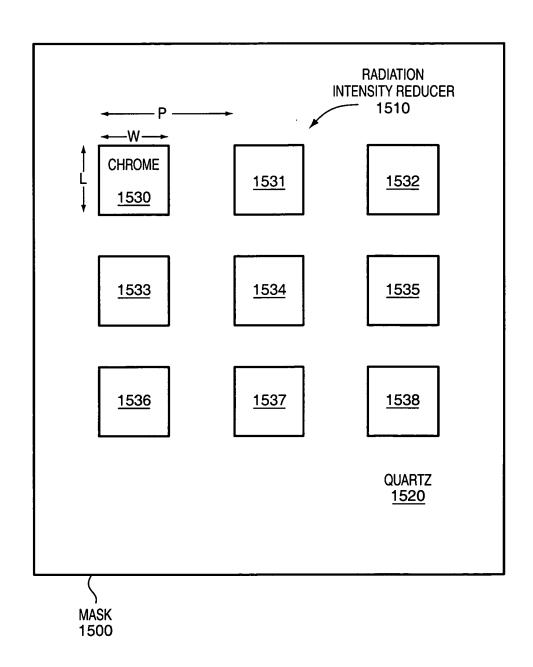


FIG. 15